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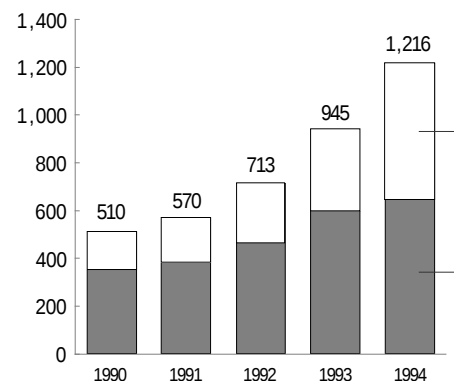
“ ”

94 33 , 24% 7 8700 ,
 76% 25 가
 93 27 7600 30% 6 5100 , 70% 21 2500
 76.5% .
 MPU MOS Micro 93%, Bipolar Digital IC가 94% 가 ,
 MOS Memory 27% 가
 Analog 6 4 7400 79%
 Analog IC Op-Amp가 , System
 Linear IC, Analog+Digital Linear IC Linear IC 가가
 97%
 13% , 45%,
 38% 가 3% .
 , Stepper Nikon · Cano ndl A/S Center가
 , Coater & Developer Wafer Cleaning St. DNS 94 4
 Wafer Cleaning St. 가
 Asher/Stripper PSC가 92 . Etcher KAM
 . Furnace/LP CVD Kokusai가 94
 8 , PE CVD AMK가 95 3

【 1】 (: 100 , %)

Discrete	462(16.7) (100)	342(16.3) (74)	120(18.0) (26)	115(2.5) (49)	235(4.5) (100)
Bipolar Digital	133(4.8) (100)	125(5.9) (94)	8(1.3) (6)	22(0.5) (73)	30(0.6) (100)
Analog	602(21.7) (100)	474(22.5) (79)	128(19.0) (21)	126(2.7) (50)	254(4.8) (100)
MOS Memory	538(19.4) (100)	227(10.8) (27)	311(46.3) (58)	4,146(90.3) (93)	4,457(84.7) (100)
MOS Micro	456(16.4) (100)	425(20.2) (93)	31(4.6) (7)	29(0.6) (48)	60(1.1) (100)
MOS Logic	473(17.0) (100)	407(19.3) (86)	66(9.7) (14)	127(2.8) (66)	193(3.7) (100)
Opto & Others	112(4.0) (100)	104(5.0) (93)	8(1.1) (7)	26(0.6) (59)	34(0.6) (100)
	2,776(100.0) (100)	2,104(100.0) (76)	672(100.0) (24)	4,591(100.0) (87)	5,263(100.0) (100)

【 1】 (: 100)

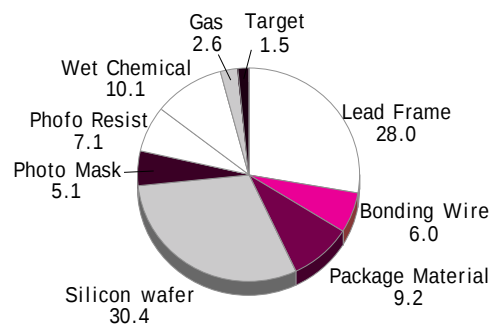
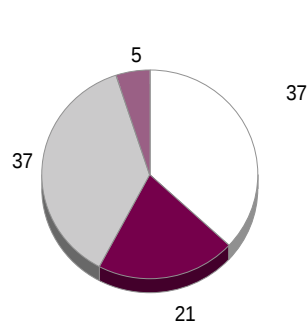


Ion Implanter Sputter Varian C.S.Eng가
 Tester(ATE)
 Symtek Aju , 가

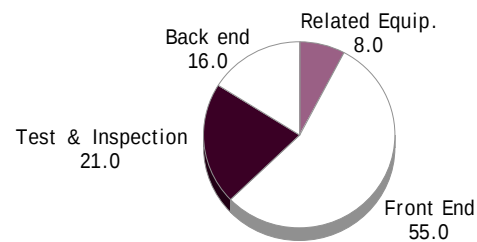
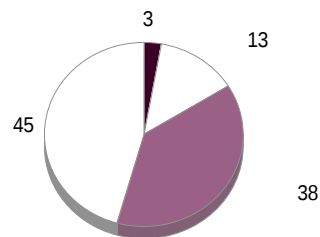
91 .
 , Test er Handler

Wafer Prober 95
 . Burn-in Sys.
 가 가
 가
 Packing System Die/Wire Bonder 가 88 Towa 95
 Making M/C 가 90
 Gas Supply Sys. 가 88 , Gas Scrubber 89
 Thermo Chamber 90 , MFC Tylan
 94
 Dry Pump Edward 94 7 Ebara 94 3
 . Burn-in Board Nano 92

【 2】 가 (1993,) (: %)
 【 3】 (1993,) (: %)



【 4】 가 (: %)
 【 5】 (1993,) (: %)



28.6%
 93 9 4500 94 12 1600
 90 68% , 94 52%
 37% 37%,
 21%, 가가 5%
 Silicon Wafer MEMC 6 8

Photo Mask Dupont 92 , 가

Photo Resist Hoechst 88 Wet Chemical

Sumitomo가 93

Specialty Gas 가 가 Dacachio 86

Lead Frame

, Wire Heraus 86

Robert Fleming

86

Package 88 EMC , 94

< 1994/12/1>